

METHOD AND INSTRUMENT FOR INSPECTION OF FINE PATTERN

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Abstract

PROBLEM TO BE SOLVED: To achieve an effective inspection of a fine pattern in a short time and at a high speed.**SOLUTION:** The position of a flat surface where a fine pattern 8 of an object 2 to be measured is fixed and the photographing position of scattered light 6 is fixed in the normal direction of the flat surface. The fine pattern 8 is irradiated with irradiation light 5 generated from a light source 4 at a specified angle θ_1 . The position of the light source 4 is moved to adjust the angle θ_1 of irradiation so that an optical pattern formed in the scattered light 6 can be photographed. Thus, a stripe pattern 30 generated from a pattern defect is detected to inspect the deformation of a pattern caused during the production period.

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